

<b>Notice of References Cited</b>	Application/Control No. 10/773,727	Applicant(s)/Patent Under Reexamination NING, XIAN JIE	
	Examiner Toniae M. Thomas	Art Unit 2822	Page 1 of 1

**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-2003/0073282	04-2003	Ning, Xian J.	438/243
	B	US-6,451,667 B1	09-2002	Ning, Xian J.	438/397
	C	US-6,559,004 B1	05-2003	Yang et al.	438/253
	D	US-6,593,185 B1	07-2003	Tsai et al.	438/253
	E	US-6,620,701 B2	09-2003	Ning, Xian J.	438/396
	F	US-6,638,830 B1	10-2003	Tsai et al.	438/397
	G	US-6,706,588 B1	03-2004	Ning, Xian J.	438/250
	H	US-6,765,255 B2	07-2004	Jin et al.	257/301
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

**FOREIGN PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N	DE 102 47 454 A1	10-2001	Germany	Ning	H01L 21/822
	O					
	P					
	Q					
	R					
	S					
	T					

**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Wolf, Ph.D., Stangley, Richard N. Tauber, Ph.D., "Dry Etching for VLSI Fabrication," Silicon Processing for the VLSI Era - Vol. 1: Process Technology, Lattice Press, 1986, pages 546-550.
	V	
	W	
	X	

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.